Surface Modification of Li-Mn-Rich Li_{1.2}Ni_{0.13}Mn_{0.54}Co_{0.13}O₂ Cathode Material by Atomic Laver Deposition

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Lithium- and manganese-rich (LMR) oxides, $xLi_2MnO_3 \cdot (1-x)LiMO_2$ (M = Mn, Ni, and Co), are promising cathode materials in terms of safety and energy density for Li-ion batteries in the era of electrified transportation and portable electronics. To improve the rate capability of this type of materials, a porous morphology is normally adopted. However the cycling stability of the cell will be challenged due to the enlarged surface area of the active materials. Recently, it has been demonstrated that surface modification using fluorine or phosphate can enhance the resistance against undesired electrode-electrolyte reactions, and consequently improve the cycle life and rate performance of the cells. Despite these improvements, the coating film thickness, composition, uniformity and conformity of the coatings can not be controlled at ease, in particular at larger scales. Atomic layer deposition (ALD) is an advanced technique to grow conformal ultrathin films with atomic layer thicknesses utilizing sequential and self-limiting surface chemical reactions.^[1] ALD has been utilized to coat anode materials,^[2] cathode materials,^[3] and electrodes^[4] for Liion batteries. Specifically, enhanced electrochemical performance had been reported in the case of Al₂O₃ coated $LiCoO_2$,^[5] $LiNi_{1/3}Mn_{1/3}Co_{1/3}O_2$ ^[6] and $Li_{1.2}Mn_{0.54}Ni_{0.13}Co_{0.13}O_2$.^[7] However, the full cell performance with the ALD coated cathode materials has not been thoroughly studied. In this paper, we will compare the Al₂O₃ and TiO₂ ALD coatings on the full cell performance of porous Li_{1.2}Ni_{0.13}Mn_{0.54}Co_{0.13}O₂ powders at various test conditions. The reactivity of the surface coated species will be also discussed.

Ultrathin Al₂O₃ and TiO₂ films were deposited on the Li_{1.2}Ni_{0.13}Mn_{0.54}Co_{0.13}O₂ powder surfaces in a viscousflow ALD reactor, using trimethylaluminum (TMA) and titanium isopropoxide (TTIP) precursors, respectively.The surface coated Al₂O₃ and TiO₂ were characterized using an aberration-corrected JEOL JEM-ARM200CF scanning transmission electron microscope (STEM) and X-ray photoelectron spectroscopy (XPS, Thermo Scientific ESCALAB 250Xi) with Al K α radiation (1486.7 eV). The electrochemistry of the ALD coated Li_{1.2}Ni_{0.13}Mn_{0.54}Co_{0.13}O₂ was studied using 2032 coin cells with Li foil or meso-carbon-micro-bead (MCMB) as the anode.

The ALD coated Al_2O_3 and TiO_2 films on the $Li_{1.2}Ni_{0.13}Mn_{0.54}Co_{0.13}O_2$ porous powder have two distinguished surface morphologies regarding to uniformity, conformity and smoothness. A higher first cycle coulombic efficiencies and improved cycling stability were attained for the ALD coated samples, which were due to the protective effect of the surface films against electrode-electrolyte reactions, in particular at the high voltages. The full cell and high-temperature performance will be discussed in the paper.

References:

1. S. M. George, *Chem. Rev.*, **110**, 111 (2010).

2. M. Q. Snyder, S. Trebukhova, B. Ravdel, M. C. Wheeler, J. DiCarlo, C. P. Tripp and W. J. DeSisto, *Solid-State Ionics*, **972**, 331 (2006).

3. Y. S. Jung, A. S. Cavanagh, A. C. Dillon, M. D. Groner, S. M. George and S. H. Lee, *J. Electrochem. Soc.*, **157**, A75 (2010).

4. Y. S. Jung, A. S. Cavanagh, L. A. Riley, S. H.

Kang, A. C. Dillon, M. D. Groner, S. M. George and S. H. Lee, *Adv. Mater.*, **22**, 2172 (2010).

5. Y. S. Jung, P. Lu, A. S. Cavanagh, C. Ban, G. H. Kim, S. H. Lee, S. M. George, S. J. Harris and A. C.

Dillon, Adv. Energy. Mater., **3**, 213 (2012).

6. L. A. Riley, S. Van Ana, A. S. Cavanagh, Y. F. Yan, S. M. George, P. Liu, A. C. Dillon and S. H. Lee, *J. Power Sources*, **196**, 3317 (2011).

7. Y. S. Jung, A. S. Cavanagh, Y. F. Yan, S. M. George and A. Manthiram, *J. Electrochem. Soc.*, **158**, A1298 (2011).